WHAT IS CLAIMED IS:

1. A process apparatus including an airtight process vessel, an exhaust system for exhausting gas from the process vessel, and a baffle plate for partitioning the process vessel into a process chamber for processing an object and an exhaust passage communicating with the exhaust system,

wherein the baffle plate has a plurality of slits through which the process chamber and the exhaust passage communicate with each other;

each slit has a tapered surface on an inner surface toward the process chamber, the tapered surface being formed to not less than 1/4 of a depth of the slit; and

an angle θ between the tapered surface and a perpendicular crossing an open end of the slit at right angles falls within a range from 5° to 30° ($5° \leqq \theta \leqq 30°$).

2. The process apparatus according to claim 1, wherein the tapered surface is formed to not less than 1/2 of the depth of the slit.

3. The process apparatus according to claim 2, wherein the baffle plate is shaped like a ring, and the plurality of slits are arranged radially on an entire circumferential surface of the baffle plate.

4. The process apparatus according to claim 2, wherein each slit extends in a radial direction of the

baffle plate, and the tapered surface extends in the radial direction of the baffle plate on either side of the slit and inclines from an opening rim of the slit, which faces the process chamber, toward the exhaust passage in which direction the opening of the slit is narrowed.

5. A process apparatus including an airtight process vessel, an exhaust system for exhausting gas from the process vessel, and a baffle plate for partitioning the process vessel into a process chamber for processing an object and an exhaust passage communicating with the exhaust system,

wherein the baffle plate has a plurality of slits through which the process chamber and the exhaust passage communicate with each other;

each slit has a tapered surface on an inner surface toward the process chamber, the tapered surface being formed to not less than 1/4 of a depth of the slit; and

each slit has an enlarged opening facing the exhaust passage, the enlarged opening extending from an opening rim of the slit, which faces the exhaust passage, toward the process chamber and having an inside diameter which is larger than a minimum inside diameter of a process-chamber-side portion of the slit on which the tapered surface is formed.

6. The process apparatus according to claim 5,

wherein the tapered surface and the enlarged opening are each formed to 1/4 to 1/2 of the depth of the slit.

7. The process apparatus according to claim 5, wherein the baffle plate is shaped like a ring, and the plurality of slits are arranged radially on an entire circumferential surface of the baffle plate.

8. The process apparatus according to claim 5, wherein each slit extends in a radial direction of the baffle plate, and the tapered surface extends in the radial direction of the baffle plate on either side of the slit and inclines from an opening rim of the slit, which faces the process chamber, toward the exhaust passage in which direction the opening of the slit is narrowed.

9. The process apparatus according to claim 8, wherein the enlarged opening and the process-chamber-side portion of the slit where the tapered surface is formed communicate with each other through a passage having a same section and size as those of a region surrounded by an inner rim of the tapered surface.

10. The process apparatus according to claim 5, wherein an angle θ between the tapered surface and a perpendicular crossing an open end of the slit at right angles falls within a range from 30° to 60° ($30° \leqq \theta \leqq 60°$).

11. The process apparatus according to claim 5, wherein a width W1 of an opening of the slit, which

faces the process chamber, and a width W2 of an opening of the slit, which faces the exhaust passage, are set so as to satisfy a condition of $1 \leqq W2/W1 \leqq 1.4$.

Add C4

Add D3

Add E3